

**Amendments to the Specification**

**Please replace the paragraph beginning at page 17, line 1, with the following rewritten paragraph:**

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FIG. 4(A) illustrates a scanning path within a region of the reticle containing ~~two~~four constituent minor stripes 44. Within the depicted region (consisting of the first two minor stripes) the minor stripes 44 (and hence the respective subfields within each minor stripe of the region) are exposed multiple times before proceeding to the next region. For comparison, FIG. 4(B) illustrates a conventional scanning path in which each minor stripe (and hence the respective subfields within each minor stripe) are exposed only once in each die. Bold arrows in the figures denote respective exposure-scanning paths.

**Please replace the paragraph beginning at page 18, line 25, with the following rewritten paragraph:**

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A scanning-exposure method according to an embodiment of the invention is shown in FIG. 4(A). Considering first the reticle 10 (~~right-hand~~left-hand portion of the figure), the uppermost (in the figure) or first minor stripe 44 in the major stripe 49 is scanned from the right-hand subfield 42-1R to the left-hand subfield 42-1L. Then, the illumination beam moves to the subfield 42-2L directly "beneath" the subfield 42-1L. From the subfield 42-2L, the illumination beam scans the second minor stripe 44 rightward to the subfield 42-2R. The first and second minor stripes 44 in this example constitute a first "region" in which the constituent minor stripes are exposed multiple times before proceeding to a second region. Hence, after scanning the second minor stripe 44, the illumination beam returns to the initial subfield 42-1R in the first minor stripe, and scanning is repeated over the subfields of the first and second minor stripes 44 in the order 42-1R to 42-1L, 42-1L to 42-2L, and 42-2L to 42-2R. The illumination beam then returns to the initial subfield 42-1R, and similar sequential scanning of the first two minor stripes is repeated two more times. After sequentially scanning the first two minor stripes a total of four times as described above, the illumination beam then proceeds to the subfield 42-3R situated "below" the subfield 42-2R in the third minor stripe 44. The illumination beam then scans the third minor stripe from the subfield 42-3R to the subfield 42-3L, and proceeds to scan the fourth minor stripe from the subfield 42-4L to the subfield 42-4R. The third and fourth minor stripes 44

A<sup>2</sup>  
(Cont'd)

constitute a second "region" in which the constituent minor stripes are exposed multiple times before proceeding to a subsequent region. Hence, after scanning the fourth minor stripe, the illumination beam scans the third and fourth minor stripes 44 three more times (for a total of four times) in a manner similar to the scanning of the first and second minor stripes. Scanning then proceeds to the fifth minor stripe (not shown but situated in the third "region"), and so on in a similar manner.

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